

AMENDMENTS TO THE CLAIMS

1-5. (Cancelled)

6. (Currently Amended) A method for manufacturing a plasma display panel (PDP) including a process for forming a metal oxide film onto a substrate of the PDP, the method comprising:

~~forming the metal oxide film in a deposition room having a degree of vacuum within a range of 1×10^{-1} Pa to 1×10^{-2} Pa; and~~

~~maintaining the degree of vacuum by~~

~~introducing inert gas into the a deposition room during deposition of the metal oxide film;~~
film;

introducing oxygen into the deposition room during deposition of the metal oxide film so as to reduce an oxygen deficiency in the metal oxide ~~film;~~ film;

introducing at least one gas selected from the group consisting of water, ~~hydrogen,~~ carbon monoxide, and carbon dioxide into the deposition room during deposition of the metal oxide film so as to increase the oxygen deficiency in the metal oxide film, wherein the oxygen or the at least one gas is introduced into the deposition room in a predetermined ~~amount;~~ amount;

controlling amounts of at least one of the inert gas and the other of the oxygen or the at least one gas to be introduced into the deposition ~~room;~~ room; and

equilibrating the amounts of the gasses introduced into the deposition room with an amount of gas exhausted from the deposition room by a vacuum exhausting system so as to control the oxygen deficiency within a predetermined range and maintain a degree of vacuum in the deposition room within a range of 1×10^{-1} Pa to 1×10^{-2} Pa.

7. (Currently Amended) The method for manufacturing the PDP of claim 6, wherein said ~~maintaining of the degree of vacuum further comprises:~~ introducing of the at least one gas comprises introducing at least one gas selected from the group consisting of water, ~~hydrogen,~~ carbon monoxide and carbon dioxide at a constant amount into the deposition ~~room;~~ room, and wherein said controlling of the amounts comprises adjusting an amount of the oxygen gas introduced into the deposition room.

8. (Currently Amended) The method for manufacturing the PDP of claim 6, wherein said ~~maintaining of the degree of vacuum further comprises:~~ introducing of oxygen comprises introducing an amount of oxygen at a constant ~~value;~~ value, and

wherein said controlling of the amounts comprises adjusting an amount of the at least one gas selected from the group consisting of water, ~~hydrogen,~~ carbon monoxide and carbon dioxide introduced into the deposition room.

9. (Currently Amended) The method for manufacturing the PDP of claim 6, wherein said ~~maintaining of the degree of vacuum further comprises:~~ introducing of oxygen comprises introducing an amount of oxygen at a constant value,

wherein said introducing of the at least one gas comprises introducing at least one gas selected from the group consisting of ~~oxygen,~~ water, ~~hydrogen,~~ carbon monoxide and carbon dioxide at a constant value into the deposition ~~room;~~ room, and

wherein said controlling of the amounts comprises adjusting an amount of the inert gas introduced into the deposition room.

10. (Cancelled)